

East 8 USPA, USPT, WPID, JPO

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1217714	etch\$ or patern\$ or remov\$	DERWENT	OR	OFF	2006/04/07 20:46
L2	5997	reticle	DERWENT	OR	ON	2006/04/07 20:46
L3	1729201	via or plug or pillar or stud or contact	DERWENT	OR	ON	2006/04/07 20:46
L4	902889	line	DERWENT	OR	ON	2006/04/07 20:47
L5	5212	exposure with (intensit\$ or level)	DERWENT	OR	ON	2006/04/07 20:47
L6	216953	resist or photoresist or mask or photomask	DERWENT	OR	ON	2006/04/07 20:47
L7	1633834	1st or 2nd or first or second or "1 st" or "2 nd"	DERWENT	OR	ON	2006/04/07 20:47
L8	21796	7 with 6	DERWENT	OR	ON	2006/04/07 20:03
L9	226362	imd or ild or interlevel\$ or interlayer\$ or "inter level\$" or "inter layer\$" or sio or "sio2" or \$silicat\$ or nitride or "si3n4" or ("si.sub.3" with "n.sub.4")	DERWENT	OR	ON	2006/04/07 20:48
L10	748687	sog or glass or quartz or dielectric or insulator or polyimide or polyamide or psg or bsg or pbsg or bpsg or oxynitride	DERWENT	OR	ON	2006/04/07 20:48
L11	637	nsg or fsg or usg	DERWENT	OR	ON	2006/04/07 20:48
L12	54	1 and 8 and 5	DERWENT	OR	ON	2006/04/07 20:07
L13	220	1 and 3 and exposur\$ and 6 and 8	DERWENT	OR	ON	2006/04/07 20:08
L14	50	(2 or 4) and 13	DERWENT	OR	ON	2006/04/07 20:08
L15	102	12 or 14	DERWENT	OR	ON	2006/04/07 20:10
L16	38	15 and (9 or 10 or 11)	DERWENT	OR	ON	2006/04/07 20:18
L17	64	15 not 16	DERWENT	OR	ON	2006/04/07 20:18
L18	711879	(etch\$ or patern\$ or remov\$).clm.	US-PGPUB; USPAT	OR	OFF	2006/04/07 20:29
L19	0	reticle.clm.	DERWENT	OR	ON	2006/04/07 20:29
L20	0	(via or plug or pillar or stud or contact).clm.	DERWENT	OR	ON	2006/04/07 20:30
L21	0	line.clm.	DERWENT	OR	ON	2006/04/07 20:29
L22	3815	reticle.clm.	US-PGPUB; USPAT	OR	ON	2006/04/07 20:30
L23	1002335	(via or plug or pillar or stud or contact).clm.	US-PGPUB; USPAT	OR	ON	2006/04/07 20:30
L24	520650	line.clm.	US-PGPUB; USPAT	OR	ON	2006/04/07 20:30

## EAST Search History

L25	5009	(exposure with (intensit\$ or level)). clm.	US-PGPUB; USPAT	OR	ON	2006/04/07 20:31
L26	113826	(resist or photoresist or mask or photomask).clm.	US-PGPUB; USPAT	OR	ON	2006/04/07 20:32
L27	2364147	(1st or 2nd or first or second or "1 st" or "2 nd").clm.	US-PGPUB; USPAT	OR	ON	2006/04/07 20:32
L28	111602	(imd or ild or interlevel\$ or interlayer\$ or "inter level\$" or "inter layer\$" or sio or "sio2" or \$silicat\$ or nitride or "si3n4" or ("si.sub.3" with "n.sub.4"))).clm.	US-PGPUB; USPAT	OR	ON	2006/04/07 20:33
L29	0	(sog or glass or quartz or dielectric or insulator or polyimide or polyamide or psg or bsg or pbsg or bpsg or oxynitride).clm.	DERWENT	OR	ON	2006/04/07 20:33
L30	305389	(sog or glass or quartz or dielectric or insulator or polyimide or polyamide or psg or bsg or pbsg or bpsg or oxynitride).clm.	US-PGPUB; USPAT	OR	ON	2006/04/07 20:33
L31	0	(nsg or fsg or usg).clm.	DERWENT	OR	ON	2006/04/07 20:34
L32	922	(nsg or fsg or usg).clm.	US-PGPUB; USPAT	OR	ON	2006/04/07 20:34
L33	553	25 with 26	US-PGPUB; USPAT	OR	ON	2006/04/07 20:34
L34	44121	26 with 27	US-PGPUB; USPAT	OR	ON	2006/04/07 20:35
L35	319	33 and 34	US-PGPUB; USPAT	OR	ON	2006/04/07 20:35
L36	58	23 and 35	US-PGPUB; USPAT	OR	ON	2006/04/07 20:36
L37	5	22 and 36	US-PGPUB; USPAT	OR	ON	2006/04/07 20:37
L38	53	36 not 37	US-PGPUB; USPAT	OR	ON	2006/04/07 20:38
L39	15808	micron.as.	US-PGPUB; USPAT	OR	ON	2006/04/07 20:38
L40	3581	albertson-t\$.in. or miller-d\$.in. or anderson-m\$.in.	US-PGPUB; USPAT	OR	ON	2006/04/07 20:39
L41	0	38 and (39 or 40)	US-PGPUB; USPAT	OR	ON	2006/04/07 20:39
L42	2650720	etch\$ or patern\$ or remov\$	US-PGPUB; USPAT	OR	ON	2006/04/07 20:46
L43	17772	reticle	US-PGPUB; USPAT	OR	ON	2006/04/07 20:46

## EAST Search History

L44	3085741	via or plug or pillar or stud or contact	US-PGPUB; USPAT	OR	ON	2006/04/07 20:46
L45	2871526	line	US-PGPUB; USPAT	OR	ON	2006/04/07 20:47
L46	50981	exposure with (intensit\$ or level)	US-PGPUB; USPAT	OR	ON	2006/04/07 20:47
L47	529353	resist or photoresist or mask or photomask	US-PGPUB; USPAT	OR	ON	2006/04/07 20:47
L48	3993869	1st or 2nd or first or second or "1 st" or "2 nd"	US-PGPUB; USPAT	OR	ON	2006/04/07 20:47
L49	399138	imd or ild or interlevel\$ or interlayer\$ or "inter level\$" or "inter layer\$" or sio or "sio2" or \$silicat\$ or nitride or "si3n4" or ("si.sub.3" with "n.sub.4")	US-PGPUB; USPAT	OR	ON	2006/04/07 20:48
L50	1202030	sog or glass or quartz or dielectric or insulator or polyimide or polyamide or psg or bsg or pbsg or bpsg or oxynitride	US-PGPUB; USPAT	OR	ON	2006/04/07 20:48
L51	6446	nsg or fsg or usg	US-PGPUB; USPAT	OR	ON	2006/04/07 20:49
L52	4338	46 with 47	US-PGPUB; USPAT	OR	ON	2006/04/07 20:49
L53	1089277	42 same (44 or 45 or 49 or 50 or 51)	US-PGPUB; USPAT	OR	ON	2006/04/07 20:51
L54	436	52 same 53	US-PGPUB; USPAT	OR	ON	2006/04/07 20:51
L55	16	43 same 54	US-PGPUB; USPAT	OR	ON	2006/04/07 20:53
L56	143	54 same 44	US-PGPUB; USPAT	OR	ON	2006/04/07 20:54
L57	130660	47 with 48	US-PGPUB; USPAT	OR	ON	2006/04/07 20:55
L58	105	54 same 57	US-PGPUB; USPAT	OR	ON	2006/04/07 20:56
L59	32	56 same 58	US-PGPUB; USPAT	OR	ON	2006/04/07 20:56
L60	27	59 not 55	US-PGPUB; USPAT	OR	ON	2006/04/07 21:00
L61	78	58 not 60	US-PGPUB; USPAT	OR	ON	2006/04/07 21:08
L62	450846	nm or nms or nanometer or "nano meter"	US-PGPUB; USPAT	OR	ON	2006/04/07 21:09
L63	57262	62 with (49 or 50 or 51)	US-PGPUB; USPAT	OR	ON	2006/04/07 21:10

## EAST Search History

L64	1791	63 same 42 same 44 same 47	US-PGPUB; USPAT	OR	ON	2006/04/07 21:11
L65	7267	42 with 63	US-PGPUB; USPAT	OR	ON	2006/04/07 21:11
L66	689	64 same 65	US-PGPUB; USPAT	OR	ON	2006/04/07 21:12
L67	309	66 and bit	US-PGPUB; USPAT	OR	ON	2006/04/07 21:26
L68	2935268	line or wiring or metalization or metallization	US-PGPUB; USPAT	OR	ON	2006/04/07 21:26
L69	279	66 same 68	US-PGPUB; USPAT	OR	ON	2006/04/07 21:28
L70	180	69 same line	US-PGPUB; USPAT	OR	ON	2006/04/07 21:28
L71	79	70 same bit	US-PGPUB; USPAT	OR	ON	2006/04/07 21:38
L72	58	70 same (dram or sram or mram or feram or fram or ram or memory or memories)	US-PGPUB; USPAT	OR	ON	2006/04/07 21:39
L73	53	71 not 72	US-PGPUB; USPAT	OR	ON	2006/04/07 21:39